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Chemical Vapour Deposition of Titanium Chalcogenides and Pnictides and Tungsten Oxide Thin Films

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Electronic Supplementary Information

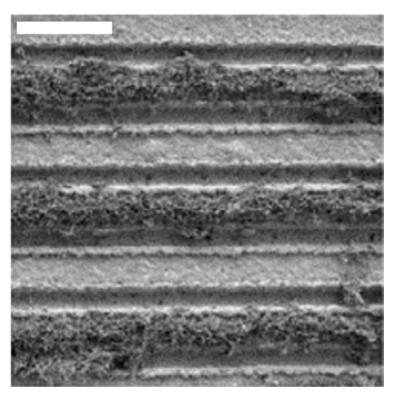


Fig. S1: SEM of a WO₃ film deposited by CVD onto an electrode array with an applied field of 10 V dc; scale bar: 2 microns